

AUTHOR CORRECTION OPEN

Author correction: Wafer-scale two-dimensional ferromagnetic Fe_3GeTe_2 thin films grown by molecular beam epitaxy

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The title of this Article has been amended from “Wafer-scale two-dimensional ferromagnetic Fe_3GeTe_2 thin films were grown by molecular beam epitaxy” to “Wafer-scale two-dimensional ferromagnetic Fe_3GeTe_2 thin films grown by molecular beam epitaxy”.

Also, the surname of one of the authors has been corrected from “Yichao Zhou” to “Yichao Zou”.

This has now been corrected in the HTML and PDF versions of this article.



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